Timetable

CT: Contributed Talk, IT: Invited Talk.

Thursday, December 12th

8:30–8:55	**Registration**		
8:55–9:00	**Welcome remarks**		
9:00–9:50	IT	**T. Minea** Université Paris-Saclay	Plasma behavior in pulsed magnetrons and new trends for plasma excitation
9:50–10:20	**Coffee break**		
Session:	**Microstructural and textural control**		
10:20–11:10	IT	**N. Martin** FEMTO-ST	Structuring of thin films combining reactive gas pulsing and GLAD
11:10–11:30	CT	**J. Müller** University of Namur	In silico optimization of reactively sputtered meso-porous titanate-based thin films by genetic algorithm
11:30–11:50	CT	**K. Solanki** Université de Poitiers	Real-time growth monitoring of ultrathin Ag layers: impact of N_2 additives and seed layers on morphological evolution
11:50–12:10	CT	**T. Suszko** Koszalin University of Technology	MeMC/a-C:H type coatings with nanocolumnar, composite structure-synthesis and some properties
12:10–12:40	**Presentation of the posters (first group)**		
12:40–13:50	**Lunch**		
13:50–14:25	**Presentation of the posters (second group)**		
14:25–14:45	CT	**S. Frick** EMPA	Accelerating oxynitride coating development: Combinatorial investigation on the Al-Si-O-N system
14:45–15:05	CT	**F. Farahani** Ghent University	Do impurities have an influence on the phase composition of deposited tungsten films?

Session:	Emerging techniques for reactive sputtering		
15:05–15:55	IT	**A. Shukurov** Charles University	Reactive sputter-driven synthesis of transition metal nanoparticles and nanofluids
15:55–16:25	**Coffee break**		
16:25–16:45	CT	**P. Baroch** University of West-Bohemia	High-rate reactively sputtered Cu_2O thin films post-treated with high-power infrared laser
16:45–17:05	CT	**C. Schiffers** CemeCon AG	HiPIMS coatings for sub-micro tools for AI applications
17:05–17:25	CT	**P. Vašina** Masaryk University	Exploring different models of operation of multipulse HiPIMS
20:00–22:30	**Conference dinner**		

Session:	Poster presentations I		
12:10–12:15	P	**D. Loch** Trumpf Hüttinger GmbH	Silicon Dioxide Coatings by Reverse Pulse HIPIMS
12:15–12:20	P	**A. Debrabandere** Ghent University	Real-time in-situ sheet resistance measurements to study silver thin film nucleation during magnetron sputtering
12:20–12:25	P	**F. Lourens** Ruhr University Bochum	Exploring Engineered Artificial Minerals for Lithium Recovery from Recycling Slags: Insights from Thin Film Experiments
12:25–12:30	P	**J. Müller** Fraunhofer Institute for Mechanics of Materials	Reactive Superimposed HiPIMS / RF Deposition
12:30–12:35	P	**N. Rodkey** Empa	Accurate Reporting of Time-of-Flight Measurements with Gated Mass Spectrometry
12:35–12:40	P	**M. Aelbrecht** Soleras Advanced Coatings	New thermal spray ceramic NiOx(CrOx) targets for sputtering functional layers in low-E glass coatings

Session:	Poster presentations II		
13:50–13:55	P	**P. Marx** Ruhr University Bochum	Combinatorial Sputter Synthesis and Characterization of (La-)Co-based Thin-Film Spinel and Perovskite Materials Libraries
13:55–14:00	P	**E. Dobruchowska** Koszalin University of Technology	NiMo-C coatings synthesised by reactive magnetron sputtering as a catalyst for the hydrogen evolution reaction in an acidic environment
14:05–14:10	P	**E. Strods** University of Latvia	Optical and photochromic properties of yttrium oxyhydride thin films deposited by reactive magnetron sputtering
, 14:10–14:15	P	**A. le Febvrier** Linköping University	Embedding Fe Nanoparticles into CrN Films For enhancing thermoelectric properties
14:15–14:20	P	**O. Brune** Technical University of Munich	Enhancing Charge Transport in Metal (Oxy-)Nitrides for Efficient Solar Fuel Generation
14:20–14:25	P	**J. Ellingford** Plasma Quest Ltd	Conformal Coverage of Complex Topographies in a Reactive Process using Remote Plasma Sputtering

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Friday, December 13th

Session:	Energy applications and process control		
9:00–9:50	IT	**P. Eklund** Uppsala University	Thin film ceramics for Energy Applications
9:50–10:10	CT	**L.I. Wagner** Technical University of Munich	Engineering Ti-doped Ta_3N_5 Photoanodes via Reactive Magnetron Co-Sputtering for Enhanced Solar Fuel Applications
10:10–10:30	CT	**T. Kubart** Uppsala University	Superconducting NbN thin films deposited by reactive magnetron sputtering
10:30–11:00	**Coffee break**		
11:00–11:20	CT	**L. Maroto-Diaz** Gencoa Ltd.	The study of defect reduction in optical coatings produced using reactive process feedback control
11:20–11:40	CT	**J. Van Bever** Ghent University	How to converge feedback control and measure double hysteresis?
11:40–12:00	CT	**K. Choglay** Manchester Metropolitan University	Exploring the Link between Plasma Gas Speciation and the properties of TiO_xN_y Thin Films
12:00–13:30	**Lunch**		
Session:	Smart sensing and complex coatings		
13:30–14:20	IT	**F. Vaz** University Minho	Specially architectured thin films for sensing applications
14:20–14:40	CT	**A. Crovetto** Technical University of Denmark	Phosphide and phosphosulfide thin films by reactive sputtering
14:40–15:00	CT	**P. Kelly** Manchester Metropolitan University	Deposition of $BiVO_4$ Thin Films by Reactive Magnetron Co-Sputtering for Visible Light Photoelectrochemical Water Splitting
15:00–15:20	CT	**D. Depla** Ghent University	The future of RSD and reactive sputtering
15:20–15:30	**Closing ceremony**		